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Buckling and postbuckling of etching-induced wiggling in a bilayer structure with intrinsic compressive stress

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Highlights:

- Buckling and postbuckling of etching-induced wiggling in a bilayer structure is investigated.
- Mask layer includes intrinsic compressive stress while unmasked layer is selectively removed.
- Etching process is explicitly introduced via step-by-step eigenvalue buckling analysis.
- In explicit modeling of etching, wiggling behavior shows completely opposite tendencies.
- The importance of explicit modeling of etching process is confirmed.

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